

**PHOTOSENSITIVE RESIN COMPOSITION, PATTERN FORMING METHOD,
CURED FILM, LAMINATE, AND DEVICE**

ABSTRACT

There are provided a photosensitive resin composition containing at least one precursor selected from the group consisting of a polyimide precursor and a polybenzoxazole precursor, a compound having a sulfurous ester structure, and a photoradical polymerization initiator, and satisfies at least one of the following conditions 1, ..., or 3; a pattern forming method using a photosensitive film formed from the photosensitive resin composition; a cured film formed from the photosensitive resin composition; a laminate including the cured film; and a device having the cured film or the laminate.

the condition 1: the precursor contains a radically polymerizable group,

the condition 2: the compound having a sulfurous ester structure contains a radically polymerizable group, and

the condition 3: the photosensitive resin composition further contains a compound containing a radically polymerizable group, other than the precursor and the compound having a sulfurous ester structure.

[No Available Figure]